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Attorney Docket No. 108298515US3

FOR DISCUSSION PURPOSES ONLY PROPOSED CLAIM AMENDMENTS

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Whonchee Lee et al.

APPLICATION No.:

09/888,002

FILED: June 21, 2001

FOR: METHODS AND APPARATUS FOR

ELECTRICALLY AND/OR CHEMICALLY-MECHANICALLY REMOVING

CONDUCTIVE MATERIAL FROM A MICROELECTRONIC SUBSTRATE

EXAMINER: Dung V. Nguyen

ART UNIT: 3723

CONF. No: 9049

PROPOSED CLAIM AMENDMENTS

FOR DISCUSSION PURPOSES ONLY

Assistant Commissioner for Patents Washington, D.C. 20231

Sir:

In the Claims:

25. A method for removing electrically conductive material from a face surface of a microelectronic substrate, comprising:

engaging the microelectronic substrate with a polishing surface of a polishing pad:

coupling the conductive material to a source of electrical potential;

removing at least a portion of the conductive material from the microelectronic substrate by passing a varying current through the conductive material while moving at least one of the microelectronic substrate and the polishing pad relative to the other and while the microelectronic substrate is engaged with the polishing pad; and

removing gas from a region between the face surface of the microelectronic substrate and an electrode facing toward the face surface of the